SRF Cavity Preparation and Limitations

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Outline:

- Cavity Qualifying Test Limitations (Vertical Test)
 - Vertical Test Results
 - Main Limitations (Field emission, Thermal breakdown, Multipacting)
 - Not Covered (Q-disease, Trapped Magnetic Field, High Field Q-Drop)
 - Performance History
- Today's Standard Processing Procedures
 - Standard Processing Sequence (30-40 MV/m)
 - Surface cleaning, Chemistry, HPR, Heat treatment, Baking, Helium Processing
- Future Process Improvements
 - Vertical EP, Plasma Cleaning, Integrated Process Automation



When Proper Procedure and Attention to Detail Occur –



However performances are not always ideal





Characterized by an exponential drop of the Q-value

Associated with production of x-rays and emission of dark current

Today good processes and procedures can minimize or eliminate this issue but its always there at some level



SNS HB54 Qo versus Eacc Multipacting limited at 16MV/m 5/16/08 cg



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SNS HTB 54 Radiation at top plate versus Eacc 5/16/08 cg



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Field Emission from Ideal Surface

Fowler-Nordheim model





Geometrical Origin of Field Enhancement

Smooth particles show little field emission

Simple protrusions are not sufficient to explain the measured enhancement factors

Possible explanation: tip on tip (compounded enhancement)





Localized Defects











$\approx 15 \times 10 \,\mu m$



Example of Field Emittors



Fig. 11 Example of a scratch and a particle on a niobium surface.













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Example of Field Emitters



Stainless steel







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Looking Inside the Cavity During Testing



 Before onset of Radiation outside dewar

 Radiation present on detector and in CCD image



Enhancement by Absorbates

Adsorbed atoms on the surface can enhance the tunneling of electrons from the metal and increase field emission



Field Emission ? MP! And then later on Field Emission !



If this cavity is limited at this condition, what is the limiting factor? Field emission?

Ex. 17b individual



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Localized heating

Hot area increases with field

At a certain field there is a thermal runaway, the field collapses

sometimes displays a oscillator behavior

sometimes settles at a lower value

sometimes displays a hysteretic behavior





Thermal breakdown occurs when the heat generated at the hot spot is larger than that can be evacuated to the helium bath

Both the thermal conductivity and the surface resistance of Nb are highly temperature dependent between 2 and 9K







Thermal stabilities and optimal operating parameters for the Oak Ridge Spallation Neutron Source superconducting linear accelerator



Surface Resistance vs Temperature





Power Dissipation vs Temperature



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Niobium Specific Heat vs Temperature



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Heat Transfer Density (Bath-Niobium)



- Tb –Helium Bath
- Ts Niobium Surface Helium side
- q- heat density



Niobium Thermal Conductivity vs Temperature





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Thermal Conductivity of Nb





Residual Resistance Ratio

RRR is the ratio of the resistivity at 300K and 4.2K

$$RRR = \frac{r(300K)}{r(4.2K)}$$

At normal conducting and cryogenic state

RRR is related to the mean free path.

For Nb: $l(T = 4.2K) \gg 27 RRR (Å)$

RRR is related to the thermal conductivity For Nb: $I(T = 4.2K) \approx RRR / 4$ (W. m⁻¹. K⁻¹)





Breakdown field given by (very approximately):

$$H_{tb} = \sqrt{\frac{4k_T(T_c - T_b)}{r_d R_d}}$$

 κ_T : Thermal conductivity of Nb R_d : Defect surface resistance T_c : Critical temperature of Nb T_b : Bath temperature



Quenching pattern examples in the end group

Kim ORNL



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JLab T-mapping and High-Resolution Optical Inspection



Multipacting



Peak electric field



Multipacting

SNS HB54 Qo versus Eacc Multipacting limited at 16MV/m 5/16/08 cg





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Multipacting

Multipacting is characterized by an exponential growth in the number of electrons in a cavity

Multipacting requires 2 conditions:

Electron motion is periodic (resonance condition)

Impact energy is such that secondary emission coefficient is >1




Multipacting



Secondary Emission in Niobium

STUDIES OF MULTIPACTING IN AXISYMMETRIC CAVITIES FOR MEDIUM-VELOCITY BEAMS*

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More Then Just Cell Mulitpacting



for the U.S. Department of Energy



Separating MP and Field Emission Contributions to X-rays Observed



NACOAK RIDGE National Laboratory

Performance History DESY cavity experience



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Performance from my experience

- In the early 1990's gradients were mainly limited around15MV/m vertical test and 10MV/m in machines
 - Field emission dominated the performance
 - Preparation procedure
 - Bulk removal BCP, RF tuning, Degreasing, Final light BCP, DI water rinsing, Assembly
- By the mid 1990's high pressure rinse was established as a new cleaning method to reduce field emission
- Early 2000
 - Gradients had reached 20-25 MV/m vertical test which correlated to machine performance as well
 - Electropolish chemistry was reintroduced and showed gradients could be pushed to 30-35MV/m
- Today the focus is on reproducibility with occasional 40MV/m **performances**

Standard Process Generalized

- Heavy chemical etch (EP or BCP)
 - Removal of damaged surface layer (100-150um) caused by fabrication and handling
- Removal of surface contamination
 - Ultrasonic cleaning of surface with detergent and DI water, heated and or
 - Alcohol rinse of surface to remove chemical residues
- Heat treatment (600-800C in vacuum furnace)
 - Removes hydrogen from the bulk niobium to reduce the risk of Q-disease
- RF tuning and mechanical inspection
 - Last chance to prepare cavity for operational use
 - Field profile, calibration of test probes, check mechanical structure



Standard Process Generalized cont.

- Removal of surface contamination
 - Ultrasonic cleaning of surface with detergent and DI water, heated
- Light chemical etch (EP)
 - Remove any risk from damage during handling and furnace contamination
- Removal of surface contamination (chemical residues)
 - Ultrasonic cleaning
 - Alcohol rinse
- High pressure rinse (UPW) + Class 10 drying of cavity
 - Reduction of field emission sources, surface particulates
 - At least two passes over entire surface

Standard Process Generalized cont.

- Assembly of subcomponents (most hardware at this step)
 - Process of connecting subcomponents to cavity openings
 - Slow and careful steps, high level of attention to detail
 - Ionized nitrogen gas blow off (cleaning) of subcomponents and hardware
 - Assembly optimized to reduce particulate contamination into cavity surface
- High pressure rinse (UPW) + Class 10 drying of cavity
 - Last chance to clean surface and remove particulates from first assembly
 - Most critical cleaning step against field emission
 - At least two passes over entire surface
- Assembly of subcomponents (final evacuation flange)
 - Most critical assembly step no follow-up cleaning



Heat treatment (600-800C)



Details		
Temperature of hot zone	Low end 600C	Typical 800C
Vacuum	Start 1e-7 Torr	End 1e-5 Torr
Cavity cleaning	Typically - degreasing	Sometimes- Chemistry and HPR
Support structure	Moly rails or rods	
Automated controls	RGA, PLC	
Process time	6-12 hrs or more	



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Small Part Ultrasonic Cleaning Stations



- Rinse tank out
- Fill with DI water
- Add Liquid Detergent
 - Liquinox
 - Micro-90
 - Few percent by volume
- Ultrasonic agitation
 - 15-60 minutes
- Remove and rinse parts with DI water
- Blow dry
 - ionized nitrogen gas
 - Laminar flow hepa air



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Ultrasonic cleaning

- Immersion of components in DI water and detergent medium
- Wave energy forms microscopic bubbles on component surfaces. Bubbles collapse (cavitation) on surface loosening particulate matter.
- Transducer provides high intensity ultrasonic fields that set up standing waves. Higher frequencies lowers the distance between nodes which produce less dead zones with no cavitation.
- Ultrasonic transducers are available in many different wave frequencies from 18 KHz to 120 KHz, the higher the frequency the lower the wave intensity.



The Need For Material Removal





P. Kneisel



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Niobium Material Removal by Chemistry



Niobium surface after BCP

Niobium surface after EP



Hydrofluoric Acid Safety

- Hydrofluoric acid is an anomaly
 - It does not react like all other acids once absorbed into the skin
 - It absorbs deeply into skin, destroys everything in the path, then slowly releases into blood stream bonding all calcium
 - Calcium is needed to control the hart → cardiac arrest can result in 8 hours after the exposure
 - Time to proper first aid (removal of and bonding of fluorine) is the most important detail and will determine the outcome
 - Large exposures always lead to death even with first aid and medical treatment



HF Safety cont.

• Before using HF

- Ensure the lab has a functioning safety shower
- Calcium gluconate cream or equivalent
- Proper PPE to cover all exposed skin
- Additional personnel trained in providing first aid and available
- Before using a System
 - Review and understand the hazards
 - Know what to do when an accident happens



Buffered Chemical Polish (BCP)

Acid = HF (49%), HNO_3 (65%), H_3PO_4 (85%) Mixture 1:1:1, or 1:1:2 by volume typical







Use of BCP:

- 1:1:1 still used for etching of subcomponents (etch rates of 8um/min)
- 1:1:2 used for most cavity treatments
 - Mixing necessary \rightarrow reaction products at surface
 - Acid is usually cooled to 10-15C (1-3um/min) to control the reaction rate and Nb surface temperatures (reduce hydrogen absorption)





Effects of BCP on The Niobium Surface





(BCP) Systems for Cavity Etching:

- Bulk & Final chemistry
 - Bulk removal of (100-200um)
 - Final removal of (5-20um) to remove any additional damage from QA steps and produce a fresh surface



Implementation:

- Cavity held vertically
- Closed loop flow through style process, some gravity fed system designs
- Etch rate 2X on iris then equator
- Temperature gradient causes increased etching from one end to the other
- Manually connected to the cavity but process usually automated



Electropolish (EP)

Electrolyte = 1 part HF(49%), 9 parts H_2SO_4 (96%)

Reaction: Oxidation $2Nb + 5SO_4^{2-} + 5H_2O \rightarrow Nb_2O_5 + 10H^+ + 5SO_4^{2-} + 10e^-$

Reduction Nb₂O₅ + 6HF \rightarrow H₂NbOF₅ + NbO₂F 0.5H₂O + 1.5H₂O

 $NbO_2F 0.5H_2O + 4HF \rightarrow H_2NbOF_5 + 1.5H_2O$

These are not the only reactions that take place!

Nb Surface Effects After EP



Surface Roughness of Niobium





Basic Concepts of EP





 0-V1- Concentration Polarization occurs, active dilution of niobium, electrolyte resistance

• V2-V3 – Limiting Current Density, viscous layer on niobium surface

>V3 Additional Cathodic
Processes Occur, oxygen gas
generated



Cavity IV Curve not easy to interpret



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Hydrogen Gas Shielding Experiment





Electropolishing of 9-cell Resonators (Nomura Plating & KEK)



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Electropolishing Systems JLAB





Electropolishing Systems DESY





High Pressure Rinsing:



• This is still the best cleaning method against field emission!

- The need for HPR surface cleaning:
 - Entire surface contaminated after chemistry, early field emission will result if not performed
 - Effective at removing particulates on the surface after assembly steps

ISSUES:

- HPR systems are still not optimized for the best surface cleaning performance
- Surface left in a vulnerable state, wet



^{for th}3/27/06 OPS-

Average Particle Count vs Cavity Accelerating Gradient SNS High β Cavities



HPR spray heads needs to be optimized for a particular geometry!



Very effective on irises

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Equator fill with water \rightarrow too high flow rate

For a given pump displacement the nozzle opening diameter and number of nozzles sets the system pressure and flow rate

Helium Processing

- Variation of RF processing
- Keep pressure below discharge condition
- Run cavity in the field emission regime
- Push the gradient as high as the system allows
- The process in details is unknown
 - Electron spraying from FE → bombard surface → ionization of helium at around surface → destroy field emitter???
 - Controlled processing is difficult
 - Relying on field emitter locations and responses
 - Uniformity??







Cornell University Laboratory for Elementary-Particle Physics

Vertical Electropolish Proven Effective

- We have demonstrated gradients >35 MV/m in individual cells of two 9cell cavities processed with vertical EP.
- In each test the π-mode was limited by quench.







⁷¹ MRongliaGengergy

Preliminary experimental setup in RFTF



First plasma in the SNS HB cavity

300W forward 200W reflected 1e-4 torr






Radiation (before and after processing)

Radiation reduced by factor of 5 to 100 Showed promising results for in-situ processing



Integrated Process Automation

The Need!

- Cryomodules are expensive (\$M)
 - Amount of hands-on labor
 - Failure rates (sensitivity of performance to errors)
 - Material costs (increasing with time, complexity of design)
- Machine energies are increasing
 - Cryomodule numbers are increasing (100,s \rightarrow 1000's)



Integrated Process Automation

- There is hope however for reduction of failure rates and labor
 - In my opinion "Vertical EP" may be the breakthrough we needed
 - Now one can imagine combining many of the processes into a single process station or two
 - Example
 - Degreasing Assembly
 - Electropolish → Evacuation

Baking

- HPR Leak test
- Drying

